

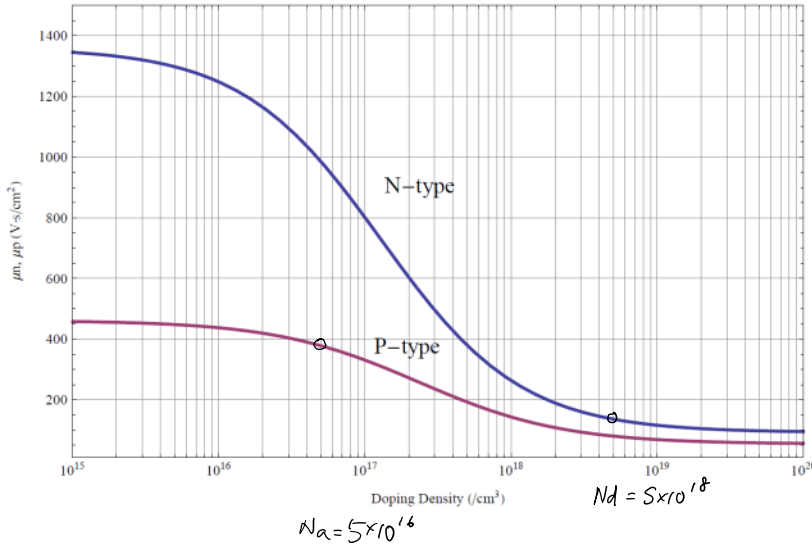
### Section 3.3: Current Flow in Semiconductors

**3.6** A young designer, aiming to develop intuition concerning conducting paths within an integrated circuit, examines the end-to-end resistance of a connecting bar 10- $\mu\text{m}$  long, 3- $\mu\text{m}$  wide, and 1  $\mu\text{m}$  thick, made of various materials. The designer considers:

- (a) intrinsic silicon
- (b)  $n$ -doped silicon with  $N_D = 5 \times 10^{16}/\text{cm}^3$
- (c)  $n$ -doped silicon with  $N_D = 5 \times 10^{18}/\text{cm}^3$
- (d)  $p$ -doped silicon with  $N_A = 5 \times 10^{16}/\text{cm}^3$
- (e) aluminum with resistivity of 2.8  $\mu\Omega/\text{cm}$

Find the resistance in each case. For intrinsic silicon, use the data in Table 3.1. For doped silicon, assume  $\mu_n = 3\mu_p = 1200 \text{ cm}^2/\text{V} \cdot \text{s}$ . (Recall that  $R = \rho L/A$ .)

*I used a more precise value for  $\mu_n$  &  $\mu_p$   
Mobility for n and p vs. Doping Density for Si*



$$(a) R = \frac{L}{\sigma} = \frac{L}{q \mu_p p + q \mu_n n}$$

$$0 = q \mu_p p + q \mu_n n$$

$$R = \frac{L}{q \mu_p p + q \mu_n n} \left( \frac{L}{wt} \right)$$

$$\frac{L}{wt} = \frac{10}{3 \times 10^{-4}} = \frac{10}{3} \times 10^4 \text{ cm}, q = 1.6 \times 10^{-19} \text{ C}$$

$$(a) \text{ intrinsic Si, } \mu_p \approx 450 \frac{\text{cm}^2}{\text{V} \cdot \text{s}}, \mu_n \approx 1350 \frac{\text{cm}^2}{\text{V} \cdot \text{s}}$$

$$R = 7.72 \times 10^9 \Omega \text{ or } 7.72 \text{ G}\Omega$$

$$(b) N_D = 5 \times 10^{18}, n = 5 \times 10^{18}, p = 4.5 \times 10^2/\text{cm}^3, \mu_n \approx 125 \frac{\text{cm}^2}{\text{V} \cdot \text{s}}$$

$$R \approx \frac{1}{q \mu_p p + q \mu_n n} \left( \frac{L}{wt} \right) = 333 \Omega$$

$$(c) N_A = 5 \times 10^{16}, p \approx 5 \times 10^{16}, \mu_p \approx 375 \frac{\text{cm}^2}{\text{V} \cdot \text{s}}$$

$$R \approx \frac{1}{q \mu_p p} \left( \frac{L}{wt} \right) = 1.1 \times 10^4 \Omega \text{ or } 11 \text{ k}\Omega$$

$$(d) R = 2.8 \times 10^{-6} \times \left( \frac{10}{3} \times 10^4 \right) = 9.3 \times 10^{-2} \Omega$$

**3.7** Contrast the electron and hole drift velocities through a 10- $\mu\text{m}$  layer of intrinsic silicon across which a voltage

of 3 V is imposed. Let  $\mu_n = 1350 \text{ cm}^2/\text{V} \cdot \text{s}$  and  $\mu_p = 480 \text{ cm}^2/\text{V} \cdot \text{s}$ .

$$E_{\text{field}} = \frac{\text{Volt}}{L};$$

$$v_{dn} = \mu_n * E_{\text{field}} /. \{ \mu_n \rightarrow 1350.0, \text{Volt} \rightarrow 3, L \rightarrow 10 * 10^{-4} \};$$

$$\text{Print}["V_d \text{ for electron} = ", v_{dn} // \text{ScientificForm} // \text{Framed}, " \text{cm/s}"]$$

$$v_{dp} = \mu_p * E_{\text{field}} /. \{ \mu_p \rightarrow 480.0, \text{Volt} \rightarrow 3, L \rightarrow 10 * 10^{-4} \};$$

$$\text{Print}["V_d \text{ for hole} = ", v_{dp} // \text{ScientificForm} // \text{Framed}, " \text{cm/s}"]$$

$$V_d \text{ for electron} = 4.05 \times 10^6 \text{ cm/s}$$

$$V_d \text{ for hole} = 1.44 \times 10^6 \text{ cm/s}$$

**3.8** Find the current that flows in a silicon bar of 10- $\mu\text{m}$  length having a 5- $\mu\text{m} \times 4\text{-}\mu\text{m}$  cross-section and having free-electron and hole densities of  $10^4/\text{cm}^3$  and  $10^{16}/\text{cm}^3$ , respectively, when a 1 V is applied end-to-end. Use  $\mu_n = 1200 \text{ cm}^2/\text{V} \cdot \text{s}$  and  $\mu_p = 500 \text{ cm}^2/\text{V} \cdot \text{s}$ .

```
Clear["Global`*"]
q = 1.6 * 10^-19
Efield =  $\frac{\text{Volt}}{L}$ ;
 $\sigma = q * \mu_n * n + q * \mu_p * p /. \{\mu_n \rightarrow 1200, \mu_p \rightarrow 500, n \rightarrow 10^4, p \rightarrow 10^{16}, \text{Volt} \rightarrow 1, L \rightarrow 10 * 10^{-4}, W \rightarrow 5 * 10^{-4}, t \rightarrow 4 * 10^{-4}\}$ 
J =  $\sigma * \text{Efield}$ ;
current =  $J * W * t /. \{\mu_n \rightarrow 1200, \mu_p \rightarrow 500, n \rightarrow 10^4, p \rightarrow 10^{16}, \text{Volt} \rightarrow 1, L \rightarrow 10 * 10^{-4}, W \rightarrow 5 * 10^{-4}, t \rightarrow 4 * 10^{-4}\}$ ;
Print["Current = ", current, " A"]
R =  $\frac{1}{\sigma} * \frac{L}{W * t} /. \{\mu_n \rightarrow 1200, \mu_p \rightarrow 500, n \rightarrow 10^4, p \rightarrow 10^{16}, \text{Volt} \rightarrow 1, L \rightarrow 10 * 10^{-4}, W \rightarrow 5 * 10^{-4}, t \rightarrow 4 * 10^{-4}\}$ ;
 $\frac{1}{R}$ ;
Print["Alternatively, R = ", R, "  $\Omega$ ; current =  $\frac{V}{R} = \frac{1}{R} =$ ",  $\frac{1}{R}$ , " A"]
1.6 * 10^-19
0.8
Current = 0.00016 A
Alternatively, R= 6250.  $\Omega$ ; current =  $\frac{V}{R} = \frac{1}{R} = 0.00016$ . A
```

**3.9** In a 10- $\mu\text{m}$ -long bar of donor-doped silicon, what donor concentration is needed to realize a current density of  $2 \text{ mA}/\mu\text{m}^2$  in response to an applied voltage of 1 V? (Note: Although the carrier mobilities change with doping concentration, as a first approximation you may assume  $\mu_n$  to be constant and use  $1350 \text{ cm}^2/\text{V} \cdot \text{s}$ , the value for intrinsic silicon.)

```
= q = 1.6 * 10^-19;
ni = 1.5 * 10^10;
Currentdensity =  $\frac{2 * 10^{-3}}{(10^{-4})^2}$ ; (* converting the unit to A/cm^2 *)
NSolve[Currentdensity == ( $N_d * q * 1350 + \frac{q * n_i^2}{N_d} * \mu_p$ ) *  $\frac{\text{Volt}}{L} /. \{\text{Volt} \rightarrow 1, L \rightarrow 10 * 10^{-4}, \mu_p \rightarrow 450\}, N_d]$ 
NSolve[Currentdensity == ( $N_d * q * 1350$ ) *  $\frac{\text{Volt}}{L} /. \{\text{Volt} \rightarrow 1, L \rightarrow 10 * 10^{-4}\}, N_d]$ 
(* neglecting minority carriers for  $\sigma$  calculation *)
= {{N_d -> 9.25926 * 10^17}, {N_d -> 81.}}
= {{N_d -> 9.25926 * 10^17}}
```

*Handwritten notes:*  
 - "from  $\mu_p$  vs  $N_A$  graph" with an arrow pointing to  $\mu_p \rightarrow 450$  in the first NSolve command.  
 - "previously missing" with an arrow pointing to  $\mu_p$  in the same command.  
 - "w/out considering the role of the minority carriers" with an arrow pointing to the second NSolve command.